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PATENT NUMBER and  
ISSUE DATE

U.S. UTILITY Patent Application

APPL. NUM 10064703	FILING DATE 08/08/2002	CLASS 427	SUBCLASS 248.11	GAU 1762	EXAMINER Meeks
<b>**APPLICANTS:</b> Lin Frank;					
<b>**CONTINUING DATA VERIFIED:</b>  THM Nme 1					
<b>** FOREIGN APPLICATIONS VERIFIED:</b>  THM Nme					
PG-PUB <input type="checkbox"/> DO NOT PUBLISH <input type="checkbox"/>		RESCIND <input type="checkbox"/>			
Foreign priority claimed <input type="checkbox"/> yes <input checked="" type="checkbox"/> no		ATTORNEY DOCKET NO			
35 USC 119 conditions met <input type="checkbox"/> yes <input checked="" type="checkbox"/> no		9458-US-PA			
Verified and Acknowledged Examiners's Initials <i>[Signature]</i>					
TITLE : Method for depositing thin film using plasma chemical vapor deposition U.S. DEPT. OF COMM. / PAT & TM-PTO-436L (Rev. 12-94)					

<b>NOTICE OF ALLOWANCE MAILED</b>		<b>CLAIMS ALLOWED</b>	
<b>ISSUE FEE</b>		<b>DRAWING</b>	
Amount Due	Date Paid	Total Claims	Print Claim for O.G.
		Sheets Drwg.	Figs. Drwg.
		Print Fig.	
<input type="checkbox"/> <b>TERMINAL DISCLAIMER</b>		<b>Application Examiner</b>	
		<b>PREPARED FOR ISSUE</b>	
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